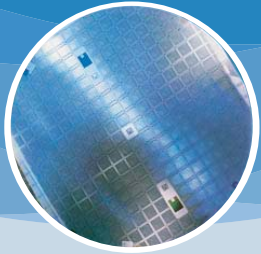


SACHEM's Bulk Silicon Etch Platform

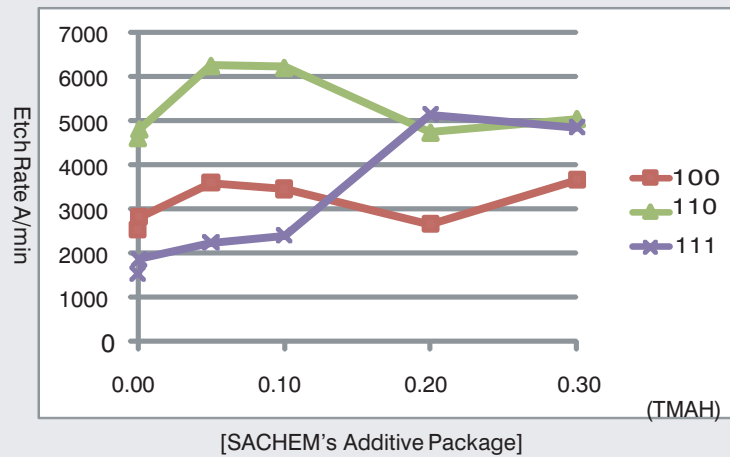
Effect of Temperature, Concentration and Additives on the Performance of TMAH, Envure LX™ TEAH, SiAn Etch™ : A Comparison



mission. critical. chemistry.

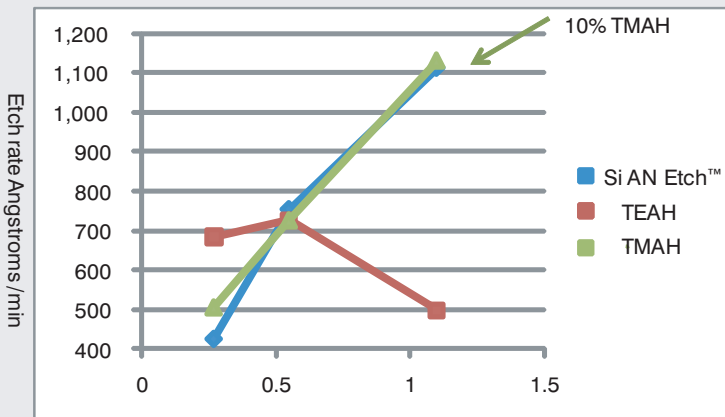
Formulated Hydroxide Etchants for Si

- Additives have a profound effect on planar selectivity in monocrystalline Si and can also affect etch rates



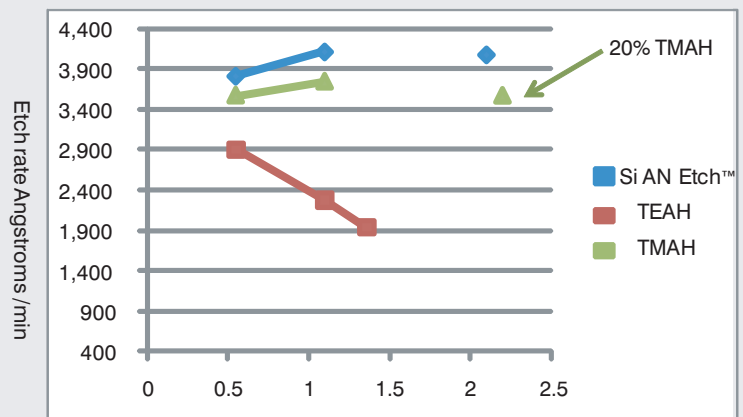
Polysilicon Etch Rates at 55°C

- Etch rate is tunable with temperature and concentration



Polysilicon Etch Rates at 75°C

- SiAn Etch™ charts similar to and performs better than TMAH



Etch Concentration M

Etch Concentration M